L Number	Hits	Search Text	DB	Time stamp
1	137	TEOS and ozone and (SACVD or (sub adj3	USPAT	2002/07/15 12:05
-		atomic))		1
2	14	(TEOS and ozone and (SACVD or (sub adj3	USPAT	2002/07/15 12:41
		atomic))) and porous		
3	1122	TEOS same (ozone O3)	USPAT;	2002/07/15 12:44
			US-PGPUB;	
			EPO; JPO	0000/07/15 13 03
8	29	(TEOS same (ozone O3)) same mgm	USPAT;	2002/07/15 13:23
			US-PGPUB;	
			EPO; JPO	2002/07/15 13:25
13	8	"5804509 <b>"</b>	USPAT;	2002/07/15 13:23
			US-PGPUB;	
			EPO; JPO	2002/07/15 13:27
18	0	"5804509" and carbon	USPAT;	2002/07/13 13:27
			US-PGPUB;	Ì
	_		EPO; JPO	2002/07/15 13:27
23	0	"11" "097533"	JPO	2002/07/15 13:27
24	0	"097533"	JPO	2002/07/15 13:27

Number   Hits   Search Text	<del></del>		O - walk March	DB	Time stamp
1					2002/07/15 14:53
1   351   ((   xerogel aerogel) and carbon) and situ   0   0   0   0   0   0   0   0   0	1	3836	(xerogel aerogel) and carbon		2002,017,20
1					
1	ا ا	65.4	((warrand sarraged) and carbon) and situ	•	2002/07/15 14:54
11   351   (((xerogel aerogel) and carbon) and situ) and (oxygen O2)   (((xerogel aerogel) and carbon) and situ) and (oxygen O2)   (((((xerogel aerogel) and carbon) and situ) and (oxygen O2)) and (sACVD porous)   (((((xerogel aerogel) and carbon) and situ) and (oxygen O2)) and (sACVD porous)   (((((xerogel aerogel) and carbon) and situ) and (oxygen O2)) and (sACVD porous)   (((((xerogel aerogel) and carbon) and situ) and (oxygen O2)) and (sACVD porous)   ((((xerogel aerogel) and carbon) and situ) and (oxygen O2)) and (sACVD porous)   ((((xerogel aerogel) and carbon) and (sBACVD porous))   ((((xerogel aerogel) and (sACVD porous))   (((((xerogel aerogel) and (sACVD porous))   (((((xerogel aerogel) and (sACVD porous))   ((((((xerogel aerogel) and (sACVD porous))   (((((((xerogel aerogel) and (sACVD porous))   ((((((((xerogel aerogel) and (sACVD porous))   ((((((((((((((((((((((((((((((((((	6	654	((xerogel aerogel) and carbon) and situ	· ·	2002, 01, 20
11   351   (((kerogel aerogel) and carbon) and situ) and (oxygen O2)   31   (((kerogel aerogel) and carbon) and situ) and (oxygen O2)   (((kerogel aerogel) and carbon) and situ) and (oxygen O2)   (((kerogel aerogel) and carbon) and situ) and (oxygen O2)   (((kerogel aerogel) and carbon) and situ) and (oxygen O2)   (((kerogel aerogel) and carbon) and situ) and (oxygen O2)   (kerogel aerogel) and carbon) and situ) and (oxygen O2)   (kerogel aerogel) and carbon) and situ) and (oxygen O2)   (kerogel aerogel) and carbon) and uspart;   (kerogel aerogel) and carbon and uspart;   (kerogel aerogel) and (sacton possible perogel)   (kerogel aerogel) and (sacton possible perogel)   (kerogel aerogel) and (acrogel) and uspart;   (kerogel aerogel) and (acrogel) are aerokide   (kerogel) aerogel)   (kerogel) aerokide   (kerogel) aerok	!				
and (oxygen O2)  and (oxygen O2)  (((xerogel aerogel) and carbon) and situ) and (oxygen O2)  149  ((((xerogel aerogel) and carbon) and situ) and (oxygen O2)) and (SACVD porous)  56  6 ((((((xerogel aerogel) and carbon) and situ) and (oxygen O2)) and (SACVD porous)  1 1503288.pn. 68546 hydrofluoric UDHF HF  - 70272 voxide nitride oxide" ono  64235 "ammonia peroxide mixture" apm H2O2 "hydrofluoric UDHF HF)  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono)  ((C4F8 ChF3) near etch\$4  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono)  ((C4F8 ChF3) near etch\$4  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono)  ((C4F8 ChF3) near etch\$4  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono)  ((C4F8 ChF3) near etch\$4  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide")  and ((C4F8 ChF3) same etch\$4  - 0 (hydrofluoric UDHF HF) find ("oxide nitride oxide" ono) and ("ammonia peroxide") and ((C4F8 ChF3) same etch\$4  - 0 (hydrofluoric UDHF HF) find ("oxide nitride oxide" ono) and ("ammonia peroxide") and ("oxide nitride oxide" ono)  - 1402 "ammonia peroxide mixture" apm and ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" apm and ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono)  - 0 ("ammonia peroxide mi		25.	(1) and situl		2002/07/15 14:54
2002/07/13 14:55	11	351		· ·	2002/0//13 11.01
16			and (oxygen 02)		
and (oxygen 02) and (oxygen 02) and carbon) and situ) and (oxygen 02) and (SACVD porcous)  6 (((((kerogel aerogel) and carbon) and situ) and (oxygen 02)) and (SACVD porcous) and TDSS and (ozone 03) 31 1 5103288.pn. hydrofluoric UDHF HF  - 0xide nitride oxide" ono - 64235 "ammonia peroxide mixture" apm H202 "hydrogen peroxide" initrute" apm H202 "hydrogen peroxide initride oxide" ono) and ("ammonia peroxide initrute" apm H202 "hydrogen peroxide") and ((C4F8 ChF3) same etch84)  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide initrute" apm H202 "hydrogen peroxide") and ((C4F8 ChF3) same etch84)  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide initrute" apm H202 "hydrogen peroxide") and etch84  - 1402 "ammonia peroxide mixture" apm USPAT; US-FGPUB; EPO; JPO USPAT					2002/07/15 14:55
21	16	351		· ·	2002/07/13 14:33
149			and (oxygen O2)		
1					2002/07/15 14:55
Commonia peroxide mixture" apm H202   Commonia peroxide mixture" apm H203   Commonia peroxide mixture" apm	21	149	((((xerogel aerogel) and carbon) and situ)		2002/07/13 14.33
Commonia peroxide mixture apm H202   Commonia peroxide amixture apm   Commonia peroxide amixture			and (oxygen O2)) and (SACVD porous)	l .	
Situ  and (exygen 02) and (SACVD porous)   US-PGPUB; EPO; JPO   USPAT; US-PGPUB; EPO; JPO   USPAT; USPAC; USPAT; USPACPUB; EPO; JPO USPAT; USPAT; USPAT; USPAT; USPAT; USPACPUB; EPO; JPO USPAT; USPAT; USPACPUB; EPO; JPO USPAT;		_			2002/07/15 15.32
and TEOS and (ozone O3)  1 103288,pn.	26	6	(((((xerogel aerogel) and carbon) and		2002/07/13 13.32
1 5103288 pn. 68546 hydrofluoric UDHF HF  70272 oxide nitride oxide" ono  64235 "ammonia peroxide mixture" apm H202 USPAT; US-PGPUB; EPO; JPO USPAT; USPAC; INDEX EPO; JPO USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAC; INDEX EPO; JPO USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAC; USPAT; USPAC; INDEX EPO; JPO USPAT; USPAT; USPAC; USPAC; USPAT; USPAC; USPA					
1002/07/13 20:59   2002/07/13 20:59   2002/07/13 20:59   2002/07/13 20:59   2002/07/13 20:59   2002/07/13 20:59   2002/07/13 20:59   2002/07/13 20:59   2002/07/13 21:11   20:59   2002/07/13 21:11   20:59				· ·	0000/07/15 15.30
- 70272   xoxide nitride oxide" ono	31	_			
- 70272	-	68546	hydrofluoric UDHF HF		2002/07/13 20:59
- 70272 toxide nitride oxide" ono  64235 "ammonia peroxide mixture" apm H2O2 "hydrogen peroxide"  - 21 (C4F8 ChF3) near etch\$4  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide" uSPAT; USP-GPUB; EPO; JPO USPAT; USP-GPUB					
Septiment   Sept		)		'	0000/07/13 01:11
EPC; JPC   USPAT; US-PGPUB;	-	70272	Voxide nitride oxide" ono		2002/07/13 21:11
- 64235 "ammonia peroxide mixture" apm H2O2 "hydrogen peroxide" USPAT; US-PGPUB; EPO; JPO USPAT;					
"hydrogen peroxide"  21 (C4F8 ChF3) near etch\$4  C4F8 ChF3) near etch\$4  C4F8 ChF3) near etch\$4  C5FGPUB; EPG; JPG  C6 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide") and (C4F8 ChF3) same etch\$4  C4F8 ChF3) same etch\$4  C5FGPUB; EPG; JPG  C7FGPUB; EPG; JPG  C7					
C4F8 ChF3   near etch\$4   EPO; JPO   USPAT; USPGUB; EPO; JPO   USPAT; USPAT; USPGUB; EPO; JPO   USPAT; USPAT; USPGUB; EP	-	64235			2002/07/13 21:08
C4F8 ChF3) near etch\$4			"hydrðgen peroxide"		
Commonia peroxide mixture				EPO; JPO	
- 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide" mixture" apm H202 "hydrogen peroxide") and ((C4F8 ChF3) near etch\$4)  - 314 (C4F8 ChF3) near etch\$4  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H202 "hydrogen peroxide") and ((C4F8 ChF3) same etch\$4)  - 77 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H202 "hydrogen peroxide") and ((C4F8 ChF3) same etch\$4)  - 77 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H202 "hydrogen peroxide") and etch\$4  - 1402 "ammonia peroxide mixture" apm USPAT; US-PGPUB; EPO; JPO USPAT;	-	21	(C4F8 Chg3) near etch\$4	USPAT;	2002/07/13 21:04
O (hydrofluoric UDHF HF) and ("oxide hitride oxide" ono) and ("ammonia peroxide" uSPAT; uS-PGPUB; EPO; JPO ((C4F8 ChF3) near etch\$4)  O (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide" uSPAT; uS-PGPUB; EPO; JPO (USPAT; uS-PGPUB; EPO; JPO (Mydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide" uSPAT; uS-PGPUB; EPO; JPO ((C4F8 ChF3) same etch\$4)  To (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide") and etch\$4  To (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide") and etch\$4  The etch\$4 and			1		
Oxide" ono) and ("ammonia peroxide" mixture" apm H202 "hydrogen peroxide") and ((C4F8 ChF3) same etch\$4)   USPAT; US-PGPUB; EPO; JPO   USPAT				EPO; JPO	
mixture" apm H202 "hydrogen peroxide") and (C4F8 ChF3) near etch\$4)  - 314 (C4F8 ChF3) near etch\$4)  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H202 "hydrogen peroxide") and (C4F8 ChF3) same etch\$4)  - 77 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H202 "hydrogen peroxide") and etch\$4  - 1402 "ammonia peroxide mixture" apm  - 1402 "ammonia peroxide mixture" apm  - 9 "ammonia peroxide mixture" apm USPAT; US-PGPUB; EPO; JPO USPAT; US-PGP	_	0	(hydrofluoric UDHF HF) and ("oxide nitride	USPAT;	2002/07/14 17:43
- 314 ((C4F8 ChF3) near etch\$4)  (C4F8 ChF3) same etch\$4  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide" us-FcPUB; EPO; JPO USPAT; US-FCPUB; EPO; JPO USPAT; US-FCPUB; EPO; JPO (C4F8 ChF3) same etch\$4  - 77 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide") and (c4F8 ChF3) same etch\$4 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide") and etch\$4  - 1402 "ammonia peroxide mixture" apm USPAT; US-FCPUB; EPO; JPO USPAT;		i	oxide" ono) and ("ammonia peroxide"	US-PGPUB;	
- 314 (C4F8 ChF3) same etch\$4  - 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H202 "hydrogen peroxide") and (C4FF ChF3) same etch\$4) - 77 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H202 "hydrogen peroxide") and etch\$4 - 1402 "ammonia peroxide mixture" apm H202 "hydrogen peroxide") and etch\$4 - 1402 "ammonia peroxide mixture" apm USPAT; US-PGPUB; EPO; JPO - 9 "ammonia peroxide mixture" apm USPAT; US-PGPUB; EPO; JPO - 139 etch\$4 near ("oxide nitride oxide" ono) - 0 "ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono) - 0 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono)) - 15 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono)) - 15 ("ammonia peroxide mixture" apm ) and ("oxide nitride oxide" ono) - 177370 "Hydrofluoric Acid" "Hydrogen fluoride" HF ("SPAT); US-PGPUB; EPO; JPO USPAT; US-PGPUB; EPO; JP	Į		mixture" apm H2O2 "hydrogen perøxide") and	EPO; JPO	
10			((C4F8 ChF3) near etch\$4)		
- 0 (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H2O2 "hydrogen peroxide") and ((C4F8 ChF3) same stch\$4) (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H2O2 "hydrogen peroxide") and etch\$4 "ammonia peroxide mixture" apm USPAT; US-PGPUB; EPO; JPO etch\$4 "ammonia peroxide mixture" apm USPAT; US-PGPUB; EPO; JPO USPAT; U	-	314	(C4F8 ChF3) same, etch\$4	USPAT;	2002/07/13 21:04
O				US-PGPUB;	
Oxide" ono) and ("ammonia peroxide mixture" apm H202 "hydrogen peroxide") and ((C4F8 ChF3) same etch\$4) ((C4F8 ChF3) same etch\$4] ((C4F8 ChF3) same etch\$4) ((C4F8 ChF3) same etch\$4] ((C4F8)				EPO; JPO	
oxide" ono) and ("ammonia peroxide mixture" apm H202 "hydrogen peroxide") and ((C4F8 ChF3) same etch\$4)  1402 "ammonia peroxide mixture" apm H202 "hydrogen peroxide") and etch\$4  1402 "ammonia peroxide mixture" apm USPAT; US-PGPUB; EPO; JPO USPAT; US	-	0	(hydrofluoric UDHF\HF) and ("oxide nitride	USPAT;	2002/07/13 21:06
((C4F8 ChF3) same etch\$4) (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H2O2 "hydrogen peroxide") and etch\$4  1402 "ammonia peroxide mixture" apm  9 "ammonia peroxide mixture" USPAT; US-PGPUB; EPO; JPO USPAT			oxide" ono) and ("ammonia peroxide	· ·	
1402   (hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm HZO2 "hydrogen peroxide") and etch\$4   ("ammonia peroxide mixture" apm   USPAT; US-PGPUB; EPO; JPO   USPAT; US-PGPUB; US-P			mixture" apm H2O2 "hydrogen peroxide") and	EPO; JPO	ļ
oxide" ono) and ("ammonia peroxide mixture" apm HZO2 "hydrogen peroxide") and etch\$4  - 1402 "ammonia peroxide mixture" apm USPAT; US-PGPUB; EPO; JPO USPAT; US-PGPUB; US-			((C4F8 ChF3) same etch\$4)		1
mixture" apm HZO2 "hydrogen peroxide") and etch\$4  "ammonia peroxide mixture" apm  9 "ammonia peroxide mixture" USPAT; US-PGPUB; EPO; JPO USPAT; US-	-	77	(hydrofluoric UDHF HF) and ("oxide nitride	USPAT;	2002/07/13 21:06
mixture" apm HZO2 "hydrogen peroxide") and etch\$4  "ammonia peroxide mixture" apm  9 "ammonia peroxide mixture" USPAT; US-PGPUB; EPO; JPO USPAT; US-			oxide" ono) and ("ammonia peroxide	US-PGPUB;	
- 1402 "ammonia peroxide mixture" apm  9 "ammonia peroxide mixture" USPAT; US-PGPUB; EPO; JPO USPAT; Near ("oxide nitride oxide" ono))  0 "ammonia peroxide mixture" and (etch\$4 USPAT; Near ("oxide nitride oxide" ono)) USPAT; US-PGPUB; EPO; JPO USPAT; US-PGPUB; EPO USPAT; US-PG		1		EPO; JPO	
US-PGPUB; EPO; JPO USPAT; US-PGPUB; EPO; JPO			1		
- 9 "ammonia peroxide mixture"  - 139 etch\$4 near ("oxide nitride oxide" ono)  - 0 "ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono))  - 0 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and ("oxide nitride oxide" ono)  - 17370 "Hydrofluoric Acid" "Hydrogen fluoride" HF ("SPAT; US-PGPUB; EPO; JPO USPAT; U	_	1402	"ammonia peroxide mixture" apm		2002/07/13 21:08
- 9 "ammonia peroxide mixture"  139 etch\$4 near ("oxide nitride oxide" ono)  - 0 "ammonia peroxide mixture" and (etch\$4					
- 139 etch\$4 near ("oxide nitride oxide" ono)  - 0 "ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono))  - 0 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and ("oxide nitride oxide" ono)  - 17370 "Hydrofluoric Acid" "Hydrogen fluoride" HF ("SPAT; US-PGPUB; EPO; JPO USPAT; US-PGPU					
- 139 etch\$4 near ("oxide nitride oxide" ono)  - 0 "ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono))  - 0 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and ("oxide nitride oxide" ono)  - 15 ("ammonia peroxide mixture" apm ) and ("oxide nitride oxide" ono)  - 17370 "Hydrofluoric Acid" "Hydrogen fluoride" HF ("SPAT; "Fluorohydric acid" "Fluoric acid" US_PGPUB; EPO; JPO USPAT; US_PGPUB; EP	-	9	"ammonia peroxide mixture"		2002/07/14 17:27
- 139 etch\$4 near ("oxide nitride oxide" ono)  - 0 "ammonia peroxide mixture" and (etch\$4			<b>\</b>		
- 0 "ammonia peroxide mixture" and (etch\$4 near ("oxide nitride oxide" ono))  - 0 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and ("oxide nitride oxide" ono)  - 17370 "Hydrofluoric Acid" "Hydrogen fluoride" HF (USPAT; "Fluorohydric acid" "Fluoric acid" US_PGPUB; EPO; JPO (USPAT; US_PGPUB; US_					
- 0 "ammonia peroxide mixture" and (etch\$4 USPAT; near ("oxide nitride oxide" ono))  - 0 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and ("oxide nitride oxide" ono)  - 17370 "Hydrofluoric Acid" "Hydrogen fluoride" HF (USPAT; "Fluorohydric acid" "Fluoric acid" US-PGPUB; EPO; JPO (USPAT; US-PGPUB; US-PGPUB; EPO; JPO (USPAT; US-PGPUB;	-	139	etch\$4 near ("oxide nitride oxide" ono)		2002/07/13 21:11
- 0 "ammonia peroxide mixture" and (etch\$4				1	
near ("oxide nitride oxide" ono))  ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  ("ammonia peroxide mixture" apm ) and (USPAT; US-PGPUB; EPO; JPO USPAT; US-PGPUB; EP			1	ł.	
- 0 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and ("oxide nitride oxide" ono)  - 2002/07/13 21:13  US-PGPUB; EPO; JPO USPAT; US-PGPUB;	-	0,		•	2002/07/13 21:12
- 0 ("ammonia peroxide mixture" apm ) and (etch\$4 near ("oxide nitride oxide" ono))  - 15 ("ammonia peroxide mixture" apm ) and ("oxide nitride oxide" ono)  - 2002/07/13 21:13  USPAT; US-PGPUB; EPO; JPO USPAT; US-PGPUB; EPO; JPO USPAT; US-PGPUB; EPO; JPO USPAT; US-PGPUB; EPO; JPO USPAT; US-PGPUB; US-PGPUB;			near ("oxide nitride oxide" ono))   \		
(etch\$4 near ("oxide nitride oxide" ond))  ("ammonia peroxide mixture" apm ) and USPAT; ("oxide nitride oxide" ono)  "Hydrofluoric Acid" "Hydrogen fluoride" HF USPAT; "Fluorohydric acid" "Fluoric acid"  US-PGPUB; EPO; JPO USPAT; US-PGPUB; US-PGPUB; US-PGPUB;					0000/07/10 01 10
- 15 ("ammonia peroxide mixture" apm ) and ("oxide nitride oxide" ono)  - 77370 "Hydrofluoric Acid" "Hydrogen fluoride" HF "Fluorohydric acid" "Fluoric acid" US-PGPUB; US-PGPUB; US-PGPUB; US-PGPUB;	-	/ 0	("ammonia peroxide mixture" apm ) and \( \)		2002/07/13 21:13
- 15 ("ammonia peroxide mixture" apm ) and USPAT; US-PGPUB; EPO; JPO USPAT; US-PGPUB; EPO; JPO USPAT; US-PGPUB; EPO; JPO USPAT; US-PGPUB; US-PGPUB; US-PGPUB; US-PGPUB; US-PGPUB;			(etch\$4 near ("oxide nitride oxide" ond))		
("oxide nitride oxide" ono)  US-PGPUB; EPO; JPO  77370 "Hydrofluoric Acid" "Hydrogen fluoride" HF USPAT; "Fluorohydric acid" "Fluoric acid" US-PGPUB;			1		1000 (00 00 00 00
- '77370 "Hydrofluoric Acid" "Hydrogen fluoride" HF USPAT; 2002/07/13 21:27 "Fluorohydric acid" US-PGPUB;	-	15			2002/07/13 21:25
- 77370 "Hydrofluoric Acid" "Hydrogen fluoride" HF USPAT; 2002/07/13 21:27 "Fluorohydric acid" US_TGPUB;	/	1	("oxide nitride oxide" ono)		
"Fluorohydric acid" "Fluoric acid" US_PGPUB;	. <b>/</b>				0000/07/10 01 07
	- 1	77370	"Hydrofluoric Acid" "Hydrogen fluoride" HF		2002/07/13 21:27
"Antisal 2B" "DEUTERIUMFLUORIDE" EPO; JPO			"Fluorohydric acid" "Fluoric acid"		
			"Antisal 2B" "DEUTERIUMFLUORIDE"	EPO; JPO	
	L	<u></u>			

			T	10000/07/14 20:47
_	31	((ammonia NH3) with (H2O2 "hydrogen	USPAT;	2002/07/14 20:47
		peroxide")) with HF	US-PGPUB;	
			EPO; JPO	
-	26	"5308400 <b>"</b>	USPAT;	2002/07/14 20:47
			US-PGPUB;	
			EPO; JPO	
_	2	5308400.pn.	USPAT;	2002/07/14 21:20
		-	US-PGPUB;	Ì
			EPO; JPO	
i <b>-</b>	206	HF and "anisotropic etching" and spacer	USPAT;	2002/07/14 21:22
		and sidewall	US-PGPUB;	
			EPO; JPO	
<u>-</u>	184	(HF and "anisotropic etching" and spacer	USPAT;	2002/07/14 21:26
		and sidewall) and gate	US-PGPUB;	
		and secondary, and general	EPO; JPO	!
_	137	TEOS and ozone and (SACVD or (sub adj3	USPAT	2002/07/15 12:05
		atomic))		
_	14		USPAT	2002/07/15 12:41
		atomic))) and porous		
_	1122		USPAT;	2002/07/15 12:44
	1122	1200 00 (000 00)	US-PGPUB;	
			EPO; JPO	
_	29	(TEOS same (ozone O3)) same mgm	USPAT;	2002/07/15 13:23
		(1200 50 (520 50, , 52 5	US-PGPUB;	
			EPO; JPO	
_	8	"5804509"	USPAT;	2002/07/15 13:25
1			US-PGPUB:	
			EPO; JPO	
_	0	"5804509" and carbon	USPAT;	2002/07/15 13:27
		do 1909 dila dalbon	US-PGPUB;	=====================================
			EPO; JPO	
_	0	"11" "097533"	JPO	2002/07/15 13:27
	0		JPO	2002/07/15 13:27
	J	U 9 1 3 3 3	1050	2002/01/13 14.32